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Solar Energy Materials & Solar Cells 72 (2002) 223–229

Solar Energy Materials
& Solar Cells

www.elsevier.com/locate/solmat

Optical improved structure of polycrystalline silicon-based thin-film solar cell

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Abstract

This paper presents an n-i-p type solar cell structure consisting of polycrystalline silicon thin film as an absorber of incident radiation and a ZnO thin film for optical improvement. The characteristics of Si layers (thickness and doping level) are designed to assure a high value of collection efficiency for photogenerated carriers. The thin films of polycrystalline silicon are obtained by CVD at a temperature of around 620°C. ZnO thin film is prepared by thermal decomposition of Zn-acetylacetonate [$\text{Zn}(\text{C}_5\text{H}_7\text{O}_2)_2$] in a vertical reactor. It is used as AR coating and as contact electrode due to its properties of high transparency (>90%) and high conductivity ($3 \times 10^{-4} \Omega \text{ cm}$). Polycrystalline silicon and ZnO films have been investigated in terms of surface morphology and grain size by AFM and XRD. © 2002 Elsevier Science B.V. All rights reserved.

Keywords: Solar cell; Thin film; Polysilicon; ZnO

1. Introduction

Solar cells based on crystalline thin films represent a promising way for simultaneously achieving good efficiency and low manufacturing cost. An important research activity in the field of good performance and low-cost solar cells is related to the types of thin-film solar cells [1], thin-film silicon growth or deposition techniques [2] and theoretical calculations [3]. The advantage of a thin-film concept is based on the fact that the semiconductor can be deposited directly on low-cost substrates. The

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